POLOS SPIN Wet Station

An extremely versatile platform for a wide range of processes. Based on the proven high quality POLOS single substrate spin processor, the modular design spin process station provides excellent value for money: full plastic construction, with high-end components, compatible with any chemical environment in a modular set-up, suitable for your specific requirement.

The seamless integration of polypropylene (optional PTFE) spin processor in the base station allows you to work with all kinds of chemicals. In the station housing various modules can be incorporated and centrally controlled for supply of chemicals and gases. Standard configurations are available for cleaning substrates as well as photo masks, photoresist coating, developing, etching and lift-off processes. Value for money: Fully automatic, accurate and repeatable processing.

Automatic dispense

Static chemical dispense through a range of adjustable nozzles in the domed lid. Adjustable back-side spray arm. Heavy-duty motor: programmable for 1 to 12.000 rpm. CW & CCW rotation allowing puddle mode. Megasonic is available as an option.

Freely programmable process

- Sequentially programmable multiple dispense lines.
- Step-less programming of various flows within a process step from 150 up to 2500 ml/min (depending on dispense line thickness). For optional integrated mixing systems, the mixing rates of the various chemicals can be programmed per step.

Source: Fraunhofer ENAS-Dr. Knut Gottfried, Precise Bulk Silicon Wet Etching 2013